



Receipt

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the application of)
Chou et al.) Examiner: Unassigned
Application No. 09/998,858) Group Art Unit: 1765
Filed: October 31, 2001) Docket No. LAM2P295
Date: March 21, 2002
For: METHOD AND APPARATUS FOR)
NITRIDE SPACER ETCH PROCESS)
IMPLEMENTING *IN SITU* INTERFEROMETRY)
ENDPOINT DETECTION AND NON-)
INTERFEROMETRY ENDPOINT MONITORING)

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States Postal Service as First Class Mail in an envelope addressed to: Commissioner for Patents, Washington, DC 20231 on March 21, 2002.

Signed: _____

Kay Harlow
Kay Harlow

REQUEST FOR CORRECTED FILING RECEIPT

Commissioner for Patents
Box: Applications
Washington, D.C. 20231

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APR 9 - 2002
TC 1700

Sir:

Enclosed is a copy of the Filing Receipt for the above-identified Patent Application. Please reprint the Filing Receipt as follows and mail the corrected copy to the undersigned.

Under Applicant(s), add inventor -- Wayne Tu, Fremont, CA. --

In the title, change the words "is situinterferometry" to -- *in situ* interferometry --.

Since this is a Patent Office typographical error, no fee should be due. However, the Commissioner is authorized to charge any fees that may be due to Deposit Account 50-0805 (Order No. LAM2P295).

Respectfully submitted,
MARTINE & PENILLA, LLP

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UNITED STATES PATENT AND TRADEMARK OFFICE

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APPLICATION NUMBER	FILING DATE	GRP ART UNIT	FIL FEE REC'D	ATTY DOCKET NO	DRAWINGS	TOT CLAIMS	IND CLAIMS
09/998,858	10/31/2001	1765	824	LAM2P295	10	20	4

CONFIRMATION NO. 6935

25920
MARTINE & PENILLA, LLP
710 LAKEWAY DRIVE
SUITE 170
SUNNYVALE, CA 94085

FILING RECEIPT



OC00000007366307

Date Mailed: 01/25/2002

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Applicant(s)

Wen-Ben Chou, Palo Alto, CA;
Shih-Yuan Cheng, Foster City, CA;

Assignment For Published Patent Application

LAM RESEARCH CORP., Fremont, CA;

Domestic Priority data as claimed by applicant

Foreign Applications

If Required, Foreign Filing License Granted 01/25/2002

Projected Publication Date: Request for Non-Publication Acknowledged

Non-Publication Request: Yes

Early Publication Request: No

Title

Method and apparatus for nitride spacer etch process implementing in situ interferometry endpoint detection and non-interferometry endpoint monitoring

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Preliminary Class

438

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Bib Data Sheet

CONFIRMATION NO. 6935

SERIAL NUMBER 09/998 858	FILING DATE 10/31/2001 RULE	CLASS 438	GROUP ART UNIT 1765	ATTORNEY DOCKET NO. LAM2P295
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APPLICANTS

Wen-Ben Chou, Palo Alto, CA;
Shih-Yuan Cheng, Foster City, CA;

** CONTINUING DATA *****

** FOREIGN APPLICATIONS *****

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** 01/25/2002

Foreign Priority claimed <input type="checkbox"/> yes <input type="checkbox"/> no	STATE OR COUNTRY CA	SHEETS DRAWING 10	TOTAL CLAIMS 20	INDEPENDENT CLAIMS 4
35 USC 119 (a-d) conditions met <input type="checkbox"/> yes <input type="checkbox"/> no <input type="checkbox"/> Met after Allowance				
Verified and Acknowledged	Examiner's Signature	Initials		

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TITLE

Method and apparatus for nitride spacer etch process implementing in situ interferometry endpoint detection and non-interferometry endpoint monitoring

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